

INDIUM OXIDE

Sputtering Target

NS6130-10-1366

Quick Facts

Product	:	Indium Oxide Sputtering Target
Stock No	:	NS6130-10-1366
CAS	:	1312-43-2
Purity	:	99.99%
Form	:	Solid

Technical Specification

Diameter	Thickness	Molecular Formula
50.8 mm ± 1mm	3 mm ± 0.5mm	In ₂ O ₃

Indium oxide sputtering target is used in applications where the deposited thin films require high transparency and electrical conductivity, such as in the production of transparent conductive electrodes for LCD displays, solar cells, and touchscreens. Indium oxide sputtering target used in various industries, including the electronics, solar, and display industries.

* This image is for graphic purposes only and does not represent the actual product.

